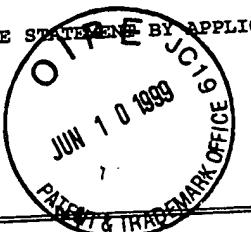


FORM PTO-1449

U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICE

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(37 CFR 1.98(b))

ATTY. DOCKET NO.
1997A006SERIAL NO.
09/237,125

APPLICANT: PADMANABAN et al.

FILING DATE: 01/26/99 GROUP 1752

U.S. PATENT DOCUMENTS

Examiner Initial		Patent Number	Issue Date	Patentee	Class	Subclass	Filing Date If Appropriate
RJA	A	US 4370405	01/25/83	O'Toole et al.	430	312	
	B	US 4575480	03/11/86	Kotani et al.	430	192	
	C	US 4636431	01/13/87	DeBergalis	428	327	
	D	US 4882260	11/21/89	Kohara et al.	430	191	
	E	US 5093414	03/03/92	Rauterkus et al.	524	813	
	F	US 5234990	08/10/93	Flaim et al.	524	609	
RJA	G	US 5294680	03/15/94	Knors et al.	524	327, GROUP 1752	

FOREIGN PATENT OR PUBLISHED FOREIGN PATENT APPLICATION

	DOCUMENT NUMBER	PUB. DATE	COUNTRY		TRANSLATION
RJA	EP 0542008	05/19/93	Europe		Yes
RJA	EP 0583205	02/16/94	Europe		Yes

OTHER DOCUMENTS (Including Author, Title, Date, Place of Publication**)

RJA		"Antireflection Layers and Planarization for Microlithography," M. Horn, SOLID STATE TECHNOLOGY, Nov. 1991, pp. 57-62
RJA		"Optimization of Optical Properties of Resist Processes," T. Brunner, Proc. SPIE, Vol. 1466, Advances in Resist Technology and Processing VIII (1991) pp. 297-307
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RJA		"High Contrast Single Layer Resists and Antireflection Layers - An Alternative to Multilayer Resist Techniques," C. Nölscher, L. Mader, M. Schneegans, Proc. SPIE Vol. 1086 Advances in Resist Technology and Processing VI (1989), pp. 242-250
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EXAMINER	R. Ashton	DATE CONSIDERED 7/27/00

EXAMINER: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.